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(54) Title: EUV SENSITIVE METAL OXIDE MATERIAL AS UNDERLAYER FOR THIN CAR TO IMPROVE PATTERN TRANSFER

(57) Abstract: Embodiments disclosed herein include a method of patterning a substrate. In an embodiment, the method comprises depositing a metal-oxo layer over a substrate, and applying a chemically amplified resist (CAR) over the metal-oxo layer. In an embodiment, the method further comprises exposing the CAR, and developing the CAR to form a pattern in the CAR. In an embodiment, the method further comprises transferring the pattern into the metal-oxo layer, and transferring the pattern into the substrate.

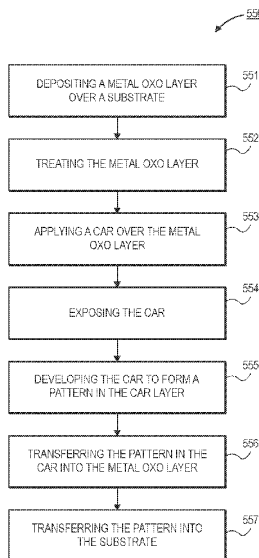


FIG. 5

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